



JPW

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant : Tse-Yao HUANG et al. Confirmation No: 4935  
Appl. No. : 10/653,882  
Filed : September 4, 2003  
Title : ETCHING METHOD AND RECIPE FOR FORMING  
HIGH ASPECT RATIO CONTACT HOLE  
  
TC/A.U. : 2812  
Examiner : O. T. Luk  
  
Docket No.: : HUAN3211/REF  
Customer No: : 23364

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is in response to the Official Action of February 1, 2005, in connection with the above-identified application. This response is timely filed.

Please amend the application as follows:

Amendments to the claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 4 of this paper.